EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S30	231	S29 and ("204" "205").clas.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/29 11:52
S29	596	diffuser and wafer and (electroplating electrochemical)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/29 11:57
S32	86	("4466864").URPN.	USPAT	OR	ON	2006/12/29 11:58
S31	404	diffuser and (semiconductor microelectronics wafer substrate) and ("204" "205").clas.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/29 12:05
S33	9	diffusing adj (plate member) and (semiconductor microelectronics wafer substrate) and ("204" "205"). clas.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/29 12:06
S1	1	10/716191	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/03 16:53
L7	17442	(diffus$3 (flow fluid) adj distribut$3) and electroplat$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/03 17:02
L8	2288	7 and ("205" "205").clas.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/03 17:02

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L9	247	8 and (diffuser diffusing adj (member plate) distributor distribut$3 adj (member plate))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/03 17:07
L11	71	9 and @py<"1999"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/03 17:11
L12	3238	7 and (semiconductor microelectronic wafer substrate) and @py<"1999"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/03 17:12
L13	1616	7 and (semiconductor microelectronic wafer) and @py<"1999"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/03 17:13
L14	10	13 and 9	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/03 17:13